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tend to lose kinetic energy and hence are more likely to stick to the cold surface. Heating the mask to a temperature higher than its surrounding causes a continuous thermophoretic effect.

Page 20, delete the whole paragraph starting at line 21 and replace it with the following new paragraph:

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In a twelfth embodiment, not illustrated, a plate matching the mask in area may be positioned underneath its patterned side except during exposure periods. The shielding plate may be spaced a distance in the range of from 5mm to 20mm from the mask and may be constructed as a particle shield according to any or all of the ninth, tenth and eleventh embodiments.

See the attached Appendix for the changes made to effect the above paragraphs.

IN THE CLAIMS:

Please enter the following amended claims:

23. (Amended) A device manufacturing method with an illumination system and projection system, comprising:

providing a substrate which is at least partially covered by a layer of radiation sensitive material;

providing a projection beam of radiation;

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using patterning structure to endow the projection beam with a pattern in its cross section;

projecting the patterned beam of radiation onto a target portion of the layer of radiation sensitive material; and

generating an electromagnetic field so as to prevent particles to become incident on an object within said illumination system or said projection system.

24. (Amended) A device manufactured in accordance with the method of Claim 23.

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26. (Amended) A mask handling device according to claim 25, wherein said particle shield comprises means for generating an electromagnetic field so as to prevent particles to become incident on at least the patterned surface of said mask.

See the attached Appendix for the changes made to effect the above claims.